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	Application No.	Applicant(s)	
	10/605,891	LANDIS, HOWARD	S.
Notice of Allowability	Examiner	Art Unit	
•	Joseph Nguyen	2815	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in the or other appropriate communi GHTS. This application is sub	is application. If not include cation will be mailed in due	ed course. THIS
1. 🔀 This communication is responsive to the amendment filed	<u>08/31/2005</u> .		
2. The allowed claim(s) is/are 1-17 and 30-33.			
 3. Acknowledgment is made of a claim for foreign priority unally all b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received:	been received. been received in Application I	No	tion from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		reply complying with the red	ąuirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			OTICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus	it be submitted.		
(a) \square including changes required by the Notice of Draftspers	on's Patent Drawing Review (PTO-948) attached	
1) 🗌 hereto or 2) 🗍 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in	the Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the			back) of
6. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	SIT OF BIOLOGICAL MATER FOR THE DEPOSIT OF BIOLO	IAL must be submitted. N DGICAL MATERIAL.	Note the
Attachment(s)			
1. Notice of References Cited (PTO-892)		mal Patent Application (PT	D-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🔲 Interview Sum Paper No /Ma	mary (PTO-413), ail Date	
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date		nendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛭 Examiner's St	atement of Reasons for Allo	wance
	9. 🗌 Other		•
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DETAILED ACTION

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Regarding claims 10-12, delete "0.1 microns" in line 12 and insert "0.1 micron".

Regarding claim 10, delete "are " in line 17 and insert "is".

Allowable Subject Matter

Claims 1-17 and 30-33 are allowed.

The following is an examiner's statement of reasons for allowance:

The reference (s) of record do not teach or suggest, either singularly or in combination at least the limitation of "the interconnect being in contact with a portion of the first rigid dielectric layer and with a portion of the second rigid dielectric layer; a structural securing means associated with the first non-rigid dielectric wiring, the structural securing means connecting together the portions of the first and second rigid dielectric layers above and below the first non-rigid dielectric wiring level so that the portions of the first and second rigid dielectric layers adjacent the interconnect are prevented from de-layering from the interconnect; and a low k dielectric layer having

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dummy fill shapes arranged above the second rigid dielectric layer" for claim 1, "dummy fill shapes associated with the first non-rigid dielectric wiring level for preventing a portion of the first or second rigid dielectric layers adjacent the interconnect from delayering from the interconnect; a low k dielectric layer having dummy fill shapes arranged above the second rigid dielectric layer; the interconnect having a line width from 0.1 microns to greater than 1 micron; and the dummy fill shapes being adjacent to the interconnect, being an alloy substantially composed of one of aluminum, copper and tungsten, and being electrically isolated from each other and the interconnect, wherein a minimum spacing between the dummy fill shapes is one to four times a minimum spacing for ordinary wires on the first non-rigid dielectric wiring level " for claim 10; "a low k dielectric layer having dummy fill shapes arranged above the second rigid dielectric layer; the interconnect having a line width from 0.1 micron to greater than 1 micron; and the dummy fill shapes being adjacent to the interconnect, being an alloy substantially composed of one of aluminum, copper and tungsten, and being electrically isolated from each other and the interconnect, wherein a minimum spacing between the dummy fill shapes is equal to a minimum spacing width for ordinary wires on the first non-rigid dielectric wiring level" for claim 11; "a low k dielectric layer having dummy fill shapes arranged above the second rigid dielectric layer; the interconnect having a line width from 0.1 micron to greater than 1 micron; and the dummy fill shapes being adjacent to the interconnect, being an alloy substantially composed of one of aluminum, copper and tungsten, and being electrically isolated from each other and the interconnect, wherein a density of the dummy fill shapes is between approximately 45%

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and 50%" for claim 12: "forming a plurality of dummy metal fill shapes in the first nonrigid dielectric wiring level in proximity to the interconnect, wherein the interconnect is in contact with a portion of the first rigid dielectric layer and with a portion of the second rigid dielectric layer; and preventing with the dummy metal fill shapes, the portions of the first and second rigid dielectric layers adjacent the interconnect from de-layering away from the interconnect" for claim 30; "forming a plurality of dummy metal fill shapes in the first non-rigid dielectric wiring level in proximity to the interconnect for preventing a portion of the first or second rigid layer adjacent the interconnect from de-layering away from the interconnect, wherein the forming of the plurality of dummy fill shapes includes forming a density of approximately 45% to 50%" for claim 31.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joseph Nguyen whose telephone number is (571) 272-1734. The examiner can normally be reached on Monday-Friday, 7:30 am- 4:30 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor. Tom Thomas can be reached on (571) 272-1664. The fax phone number for Application/Control Number: 10/605,891 Page 5

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the organization where this application or proceeding is assigned is (571) 273-8300 for regular communications.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

JN October 26, 2005.

JEROME JACKSON PRIMARY EXAMINER